

IN THE CLAIMS

Please CANCEL claims 1-18 without prejudice to or disclaimer of the recited subject matter.

Please ADD new claims 19-24, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1-18. (Cancelled)

19. (New) An exposure apparatus comprising:

a chuck for holding an object; and

an optical system for directing light from a light source to the object held by said chuck, said optical system including a multilayer film mirror which has a concave reflecting surface,

wherein an area of contacting portions of said chuck is set so that the contact portions area of the chuck is at most 10% of an area of the object held by said chuck.

20. (New) An exposure apparatus according to claim 19, wherein the area of contacting portions of said chuck is set to so that the contact portion area of the chuck is at most 2% of the area of the object held by said chuck.

21. (New) A device manufacturing method using an exposure apparatus that includes (i) a chuck for holding an object, and (ii) an optical system for directing light from a light surface to

the object held by said chuck, said optical system including a multilayer film mirror which has a concave reflecting surface, wherein an area of contacting portions of said chuck is set so that the contact portions area of the chuck is at most 10% of an area of the object held by said chuck, said method comprising the steps of:

holding the object by the chuck; and
directing the light to the object using the optical system.

22. (New) An exposure apparatus comprising:

an illumination system for illuminating a reflection mask with light from a light source, said illumination system including a multilayer film mirror which has a concave reflecting surface;

a projection optical system for projecting a pattern of the reflection mask onto an object; and

a mask chuck for holding the reflection mask,
wherein an area of contacting portions of said mask chuck is set so that the contact portions area of the mask chuck is at most 10% of an area of the reflection mask held by said mask chuck.

23. (New) An exposure apparatus according to claim 22, wherein the area of contacting portions of said mask chuck is set so that the contact portions area of the mask chuck is at most 10% of the area of the reflection mask held by said mask chuck.

24. (New) A device manufacturing method comprising the steps of:

 exposing an object using an exposure apparatus; and

 developing the object that has been exposed,

 wherein the exposure apparatus includes:

 an illumination system for illuminating a reflection mask with light from a light source, said illumination system including a multilayer film mirror which has a concave reflecting surface;

 a projection optical system for projecting a pattern of the reflection mask onto the object; and

 a mask chuck for holding the reflection mask,

 wherein an area of contacting portions of the mask chuck is set so that the contact portions area of the mask chuck is at most 10% of an area of the reflection mask held by the mask chuck.